

Supporting Information

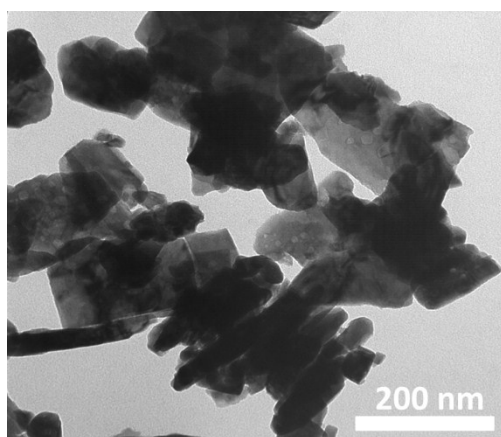
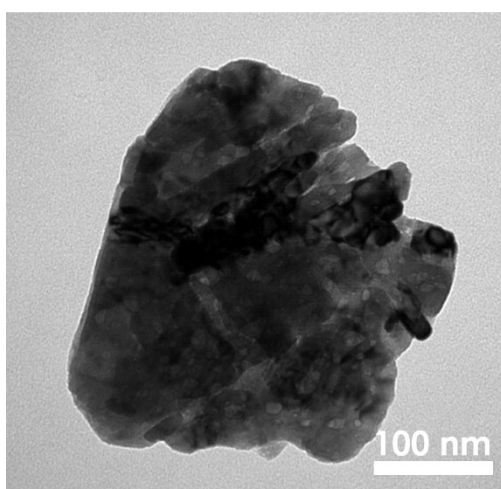
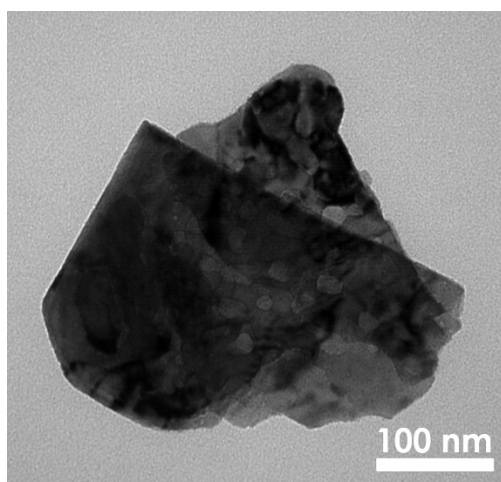
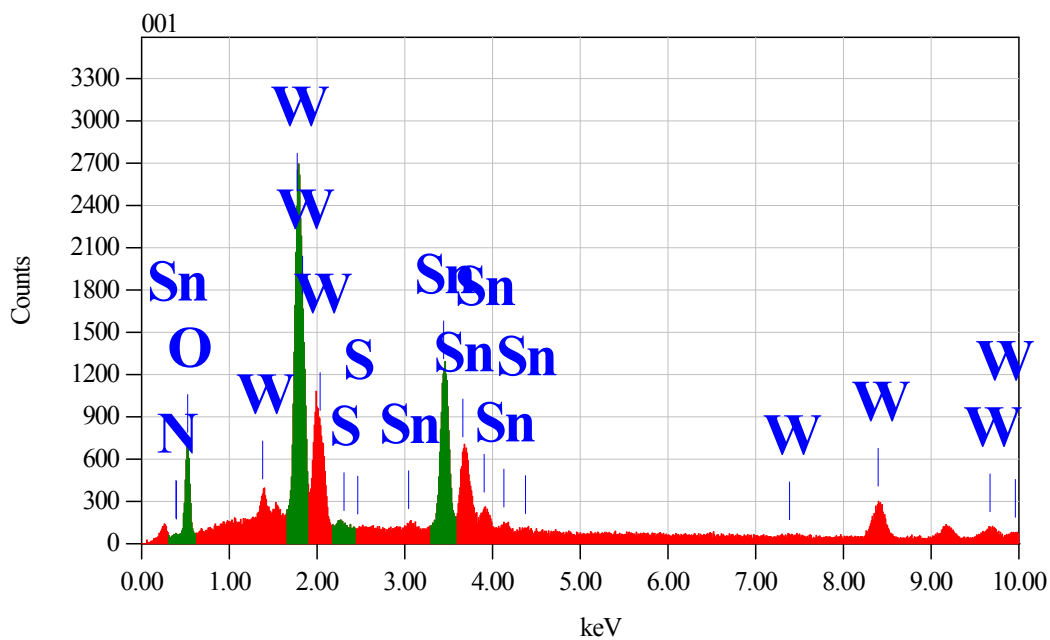


Figure S1. TEM images of the etched WO<sub>3</sub> film.



ZAF Method Standardless Quantitative Analysis

Fitting Coefficient : 0.3095

Element	(keV)	Mass%	Error%	Atom%	Compound	Mass%	Cation	K
N K*	0.392	1.44	0.26	5.07				0.8398
O K*	0.525	22.68	0.32	69.67				8.1993
S K*	2.307	0.25	0.10	0.39				0.2681
Sn L*	3.442	31.83	0.35	13.18				39.3312
W M*	1.774	43.79	0.36	11.70				51.3615
Total		100.00		100.00				

Figure S2. EDX spectra of the etched WO<sub>3</sub> film.

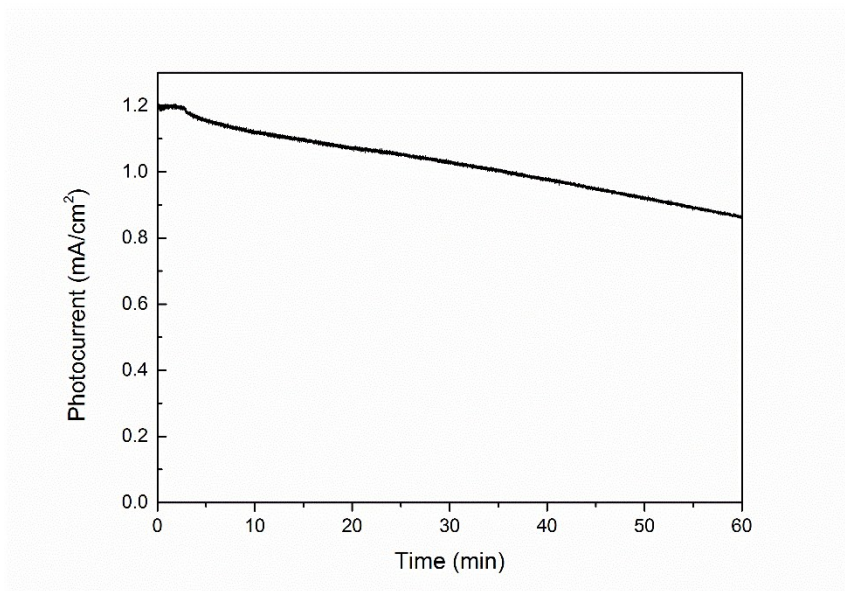


Figure S3. The long-term stability test of the etched WO<sub>3</sub> film.